

EXPOSURE APPARATUS, EXPOSURE METHOD, AND DEVICE
MANUFACTURING METHOD

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ABSTRACT

An exposure apparatus (EX) comprises a liquid immersion system (1), a first mover (4), and a prescribed member (30). The exposure apparatus (EX) exposes a substrate (P) via an optical member (FL) and a liquid (LQ). The liquid immersion
10 system (1) performs supply and recovery of the liquid (LQ). The first mover (4) can move in a first area (10), and can hold the liquid (LQ) between itself and the optical member (FL). The prescribed member (30) is removed from the first mover (4) when the first mover (4) withdraws from a position opposing the optical member (FL), and can hold the liquid (LQ) between itself and the optical member (FL).

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Fig. 1